

WHAT IS CLAIMED IS:

1. A method of forming a partial reverse active mask, comprising:  
providing a mask pattern, comprising a large active region pattern with an original dimension and a small active region pattern;

5 shrinking the large active region pattern and the small active region pattern until the small active region pattern disappears; and

enlarging the large active region pattern to a dimension slightly smaller than the original dimension.

10 2. The method according to claim 1, wherein the large active region pattern and the small active region are shrunk with a distance of about  $0.5\mu\text{m}$  to  $2.0\mu\text{m}$ .

3. The method according to claim 1, wherein the large active region pattern is enlarged with a dimension smaller than the shrinking distance.